L Number	Hits	Search Text	DB	Time stamp
2	7754	134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:24
3	7868	134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls. or 438/905.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:24
4	965	(134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls. or 438/905.ccls.) and @pd>20030227	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:25
5	9	((134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls. or 438/905.ccls.) and @pd>20030227) and ("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:28
6	61	mitsushi near2 itano	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:28
7	2	(mitsushi near2 itano) and ("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:28
-	4	(chamber adj clean$3) with (CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 10:57
-	30397420	CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:19
-	74448	(CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch$3 or clean$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:31
-	21274	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch$3 or clean$3)) and (CVD with (etch$3 or clean$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:54
-	2484	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch$3 or clean$3)) and (CVD with (etch$3 or clean$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:20
-	1924	(((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch$3 or clean$3)) and (CVD with (etch$3 or clean$3) with chamber)) and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:32
-	1	(CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene)) with (CVD with (etch$3 or clean$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:41

-	0	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch$3 or clean$3)) and ((((8/159 | 8/158 | 8/149.3 | 8/142).CCLS.) and steam$3) and (tumbl$3 or rotary or rotat$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:54
-	4	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch$3 or clean$3)) and (("4581101" | "5198634" | "5281302" | "5376234" | "5417826" | "5445712" | "5679215" | "5882424" | "5897377" | "5902403" | "5925611" | "5928963").PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:54
-	16697	"CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:20
-	15	("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and (CVD with (etch$3 or clean$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:33
-	73	("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and 134/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:29
-	146	("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and (CVD and (etch$3 or clean$3) and chamber) and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:46
-	3	"CF.sub.3 CF:CF.sub.2"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:46
-	7466	((deposition or CVD) with (etch$3 or clean$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:22
-	92	(((deposition or CVD) with (etch$3 or clean$3) with chamber)) and (("CF3CF=CF2" or C2F4 or C3H6 or C4H8) or (tetrafluoroethylene or tetrafluoroethene or perfluoroethylene or perfluoroethene) or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene) or (octafluorobutylene or octafluorobutene or perfluorobutylene or perfluorobutene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:55
-	6	(((deposition or CVD) with (etch$3 or clean$3) with chamber)) and (cleaning adj gas with (("CF3CF=CF2" or C2F4 or C3H6 or C4H8) or (tetrafluoroethylene or tetrafluoroethene or perfluoroethylene or perfluoroethene) or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene) or (octafluorobutylene or octafluorobutene or perfluorobutylene or perfluorobutene)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:27
-	2484	(((deposition or CVD) with (etch$3 or clean$3) with chamber)) and (CVD with (etch$3 or clean$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:33